ABSTRACT

There is provided a technique that includes: (A) supplying a modifying agent to a substrate including a first surface and a second surface to form an inhibitor layer on the first surface; and (B) supplying a film-forming agent to the substrate after forming the inhibitor layer on the first surface to form a film on the second surface, wherein a width of an inhibitor molecule constituting the inhibitor layer is defined as WI, a spacing of adsorption sites on the first surface is defined as DA, a width of a molecule X constituting a predetermined substance contained in the film-forming agent is defined as WP, wherein WP>DA-WI is satisfied when WI is smaller than DA, and wherein WP>DAx-WI is satisfied when WI is larger than DA, where x is a smallest integer that satisfies WI<DAx.

FIG. 6a – FIG. 6c